

# Sakari Sintonen

## List of Publications by Year in descending order

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32  
papers

698  
citations

623188

14  
h-index

552369

26  
g-index

32  
all docs

32  
docs citations

32  
times ranked

1139  
citing authors

#	ARTICLE	IF	CITATIONS
1	Mechanical and optical properties of as-grown and thermally annealed titanium dioxide from titanium tetrachloride and water by atomic layer deposition. <i>Thin Solid Films</i> , 2021, 732, 138758.	0.8	17
2	Synchrotron radiation X-ray topography and defect selective etching analysis of threading dislocations in halide vapor phase epitaxy GaN crystal grown on ammonothermal seed. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SCCB19.	0.8	4
3	Tribological properties of thin films made by atomic layer deposition sliding against silicon. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2018, 36, .	0.9	7
4	Defects in Single Crystalline Ammonothermal Gallium Nitride. <i>Advanced Electronic Materials</i> , 2017, 3, 1600496.	2.6	40
5	Top-seeded solution growth of SrTiO <sub>3</sub> single crystals virtually free of mosaicity. <i>Journal of Crystal Growth</i> , 2017, 468, 305-310.	0.7	5
6	Aluminum oxide/titanium dioxide nanolaminates grown by atomic layer deposition: Growth and mechanical properties. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017, 35, .	0.9	38
7	Microscratch testing method for systematic evaluation of the adhesion of atomic layer deposited thin films on silicon. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2016, 34, .	0.9	21
8	Preparation of deep UV transparent AlN substrates with high structural perfection for optoelectronic devices. <i>CrystEngComm</i> , 2016, 18, 3488-3497.	1.3	62
9	Thermal conductivity of amorphous Al <sub>2</sub> O <sub>3</sub> /TiO <sub>2</sub> nanolaminates deposited by atomic layer deposition. <i>Nanotechnology</i> , 2016, 27, 445704.	1.3	27
10	Incorporation and effects of impurities in different growth zones within basic ammonothermal GaN. <i>Journal of Crystal Growth</i> , 2016, 456, 43-50.	0.7	20
11	Evolution of impurity incorporation during ammonothermal growth of GaN. <i>Journal of Crystal Growth</i> , 2016, 456, 51-57.	0.7	13
12	Synchrotron X-ray diffraction topography study of bonding-induced strain in silicon-on-insulator wafers. <i>Thin Solid Films</i> , 2016, 603, 435-440.	0.8	2
13	Nanotribological, nanomechanical and interfacial characterization of atomic layer deposited TiO <sub>2</sub> on a silicon substrate. <i>Wear</i> , 2015, 342-343, 270-278.	1.5	13
14	Effect of growth temperature on the epitaxial growth of ZnO on GaN by ALD. <i>Journal of Crystal Growth</i> , 2014, 398, 18-22.	0.7	19
15	Aluminum oxide from trimethylaluminum and water by atomic layer deposition: The temperature dependence of residual stress, elastic modulus, hardness and adhesion. <i>Thin Solid Films</i> , 2014, 552, 124-135.	0.8	155
16	X-ray reflectivity characterization of atomic layer deposition Al <sub>2</sub> O <sub>3</sub> /TiO <sub>2</sub> nanolaminates with ultrathin bilayers. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2014, 32, .	0.9	28
17	Thermal and plasma enhanced atomic layer deposition of SiO <sub>2</sub> using commercial silicon precursors. <i>Thin Solid Films</i> , 2014, 558, 93-98.	0.8	66
18	Diamond-like carbon (DLC) thin film bioelectrodes: Effect of thermal post-treatments and the use of Ti adhesion layer. <i>Materials Science and Engineering C</i> , 2014, 34, 446-454.	3.8	30

#	ARTICLE	IF	CITATIONS
19	Synchrotron radiation x-ray topography and defect selective etching analysis of threading dislocations in GaN. Journal of Applied Physics, 2014, 116, 083504.	1.1	37
20	Defect structure of a free standing GaN wafer grown by the ammonothermal method. Journal of Crystal Growth, 2014, 406, 72-77.	0.7	13
21	Large-area analysis of dislocations in ammonothermal GaN by synchrotron radiation X-ray topography. Applied Physics Express, 2014, 7, 091003.	1.1	20
22	Fabrication of GaN structures with embedded network of voids using pillar patterned GaN templates. Journal of Crystal Growth, 2013, 370, 42-45.	0.7	2
23	Evaluation of critical thickness of GaP <sub>0.98</sub> N <sub>0.02</sub> layer on GaP substrate by synchrotron X-ray diffraction topography. Thin Solid Films, 2013, 534, 680-684.	0.8	5
24	Analysis of Dislocations Generated during Metal-Organic Vapor Phase Epitaxy of GaN on Patterned Templates. Japanese Journal of Applied Physics, 2013, 52, 01AF01.	0.8	2
25	Analysis of threading dislocations in void shape controlled GaN re-grown on hexagonally patterned mask-less GaN. Journal of Crystal Growth, 2012, 344, 59-64.	0.7	14
26	Effect of GaN cap thickness on carrier dynamics in InGaN quantum wells. Physica Status Solidi C: Current Topics in Solid State Physics, 2012, 9, 727-729.	0.8	2
27	Synchrotron radiation X-ray topography and X-ray diffraction of homoepitaxial GaN grown on ammonothermal GaN. Physica Status Solidi C: Current Topics in Solid State Physics, 2012, 9, 1630-1632.	0.8	7
28	MOCVD growth and characterization of near-surface InGaN/GaN single quantum wells for non-radiative coupling of optical excitations. Physica Status Solidi C: Current Topics in Solid State Physics, 2012, 9, 1667-1669.	0.8	4
29	X-ray diffraction study of GaN grown on patterned substrates. Physica Status Solidi C: Current Topics in Solid State Physics, 2011, 8, 1524-1527.	0.8	2
30	Patterning of sapphire/GaN substrates. Physica Status Solidi C: Current Topics in Solid State Physics, 2011, 8, 1509-1512.	0.8	11
31	Characterization of InGaN/GaN and AlGaIn/GaN superlattices by X-ray diffraction and X-ray reflectivity measurements. Physica Status Solidi C: Current Topics in Solid State Physics, 2010, 7, 1790-1793.	0.8	4
32	An investigation of structural properties of GaN films grown on patterned sapphire substrates by MOVPE. Physica B: Condensed Matter, 2009, 404, 4911-4915.	1.3	8